

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/776,615	02/12/2004	Tadataka Edamura	046124-5271	3944
55694	7590 04/06/2006		EXAMINER	
DRINKER BIDDLE & REATH (DC)			LANE, JEFFREY D	
1500 K STRE	ET, N.W.		ART UNIT	PAPER NUMBER
WASHINGTON, DC 20005-1209		2828		

DATE MAILED: 04/06/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/776,615	EDAMURA ET AL.				
Office Action Summary	Examiner	Art Unit				
	Jeffrey D. Lane	2828				
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 16(a). In no event, however, may a reply be tim rill apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONEI	l. lely filed the mailing date of this communication. (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 23 Ma	<u>arch 2006</u> .	•				
•	action is non-final.					
3) Since this application is in condition for allowan	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims						
4) ⊠ Claim(s) <u>1-9</u> is/are pending in the application. 4a) Of the above claim(s) <u>1-6 and 9</u> is/are withd 5) □ Claim(s) is/are allowed. 6) ⊠ Claim(s) <u>7 and 8</u> is/are rejected. 7) □ Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/or	r election requirement.					
Application Papers	•					
9) The specification is objected to by the Examiner 10) The drawing(s) filed on 12 February 2004 is/are Applicant may not request that any objection to the construction Replacement drawing sheet(s) including the correction 11) The oath or declaration is objected to by the Examiner	e: a)⊠ accepted or b)⊡ objected drawing(s) be held in abeyance. See ion is required if the drawing(s) is obj	e 37 CFR 1.85(a). ected to. See 37 CFR 1.121(d).				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau * See the attached detailed Office action for a list of	s have been received. s have been received in Application ity documents have been received I (PCT Rule 17.2(a)).	on No ed in this National Stage				
Attachment(s)						
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 7/9/04. 	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:					

Art Unit: 2828

DETAILED ACTION

Election/Restrictions

1. Claims 1-6 and 9 are withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected species, there being no allowable generic or linking claim. Election was made **without** traverse in the reply filed on 3/23/06.

Specification

2. The lengthy specification has not been checked to the extent necessary to determine the presence of all possible minor errors. Applicant's cooperation is requested in correcting any errors of which applicant may become aware in the specification.

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.
- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 4. Claims 7 and 8 are rejected under 35 U.S.C. 102(e) as being anticipated by Chang et al. (US 2004/0161006).

Art Unit: 2828

As for claim 7 Chang discloses in figure 8, a quantum cascade laser comprising (See paragraph [0027]): a semiconductor substrate formed of GaAs 800; and an active layer 830, disposed on said semiconductor substrate 800 and having a plurality of quantum well (See figure 7) light emitting layers, generating light by means of intersubband transitions in a quantum well structure (See figure 7), and a plurality of injection layers, respectively disposed between the plurality of quantum well light emitting layers and forming a cascade structure along with said quantum well light emitting layers; and wherein said quantum well light emitting layers and said injection layers of said active layer are formed to contain group III-V compound semiconductors, each containing, as the group V elements, N and at least one element selected from the group consisting of As. P, and Sb (See Paragraph [0046]).

As for claim 8 Chang discloses, The quantum cascade laser according to claim 7, wherein the composition ratio of N in said group III-V compound semiconductor is no less than 0.1% and no more than 40% (See Paragraph [0042]).

5. Claims 7 and 8 are rejected under 35 U.S.C. 102(e) as being anticipated by Dapkus (US 6621842).

As for claim 7 Dapkus discloses, a quantum cascade laser comprising: a semiconductor substrate formed of GaAs (See Column 8 line 6); and an active layer (fig 2B), disposed on said semiconductor substrate and having a plurality of quantum well light emitting layers, generating light by means of intersubband transitions in a quantum well structure (fig 2B), and a plurality of injection layers, respectively disposed between the plurality of quantum well light emitting layers and forming a cascade structure along

Art Unit: 2828

with said quantum well light emitting layers; and wherein said quantum well light emitting layers and said injection layers of said active layer are formed to contain group III-V compound semiconductors, each containing, as the group V elements, N and at least one element selected from the group consisting of As, P, and Sb (See Column 5 lines 4,5).

As for claim 8 Dapkus discloses, The quantum cascade laser according to claim 7, wherein the composition ratio of N in said group III-V compound semiconductor is no less than 0.1% and no more than 40% (See Column 5 lines 4,5).

6. Claim 7 rejected under 35 U.S.C. 102(b) as being anticipated by Spruytte et al. (2002/0075920). Spruytte discloses in figure 2, a quantum cascade laser comprising: a semiconductor substrate formed of GaAs (42); and an active layer (46), disposed on said semiconductor substrate and having a plurality of quantum well light emitting layers, generating light by means of intersubband transitions in a quantum well structure (left side), and a plurality of injection layers, respectively disposed between the plurality of quantum well light emitting layers and forming a cascade structure along with said quantum well light emitting layers; and wherein said quantum well light emitting layers and said injection layers of said active layer are formed to contain group III-V compound semiconductors, each containing, as the group V elements, N and at least one element selected from the group consisting of As, P, and Sb (GalnNAs).

Application/Control Number: 10/776,615 Page 5

Art Unit: 2828

Conclusion

7. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Taylor (US 6849866) discloses using a GaAs substrate and controlling the ratio of N doping.

Art Unit: 2828

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Jeffrey D. Lane whose telephone number is (571) 272-1676. The examiner can normally be reached on Monday thru Friday 8:30 to 5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Minsun Harvey can be reached on (571) 272-1835. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Jeffrey D Lane Examiner Art Unit 2828

JDL

Armond Project